

Douglas W Barlage

List of Publications by Year in descending order

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#	ARTICLE	IF	CITATIONS
1	Electrical Comparison of HfO_2 and ZrO_2 Gate Dielectrics on GaN. IEEE Transactions on Electron Devices, 2013, 60, 4119-4124.	1.6	21
2	Schottky barrier source-gated ZnO thin film transistors by low temperature atomic layer deposition. Applied Physics Letters, 2013, 103, .	1.5	14
3	High Breakdown Strength Schottky Diodes Made from Electrodeposited ZnO for Power Electronics Applications. ACS Applied Electronic Materials, 2019, 1, 13-17.	2.0	14
4	Capacitance Modeling and Characterization of Planar MOSCAP Devices for Wideband-Gap Semiconductors With High- κ Dielectrics. IEEE Transactions on Electron Devices, 2012, 59, 2662-2666.	1.6	11
5	Interfacial Contact Effects in Top Gated Zinc Oxide Thin Film Transistors Grown by Atomic Layer Deposition. IEEE Transactions on Electron Devices, 2016, 63, 3540-3546.	1.6	11
6	Fractal Loop Inductors. IEEE Transactions on Magnetics, 2015, 51, 1-8.	1.2	10
7	Low residual donor concentration and enhanced charge transport in low-cost electrodeposited ZnO. Journal of Materials Chemistry C, 2016, 4, 2279-2283.	2.7	8
8	A Photogenerated Silicon Plasma Waveguide Switch and Variable Attenuator for Millimeter-Wave Applications. IEEE Transactions on Microwave Theory and Techniques, 2021, 69, 5393-5403.	2.9	8
9	High-mobility solution-processed zinc oxide thin films on silicon nitride. Physica Status Solidi - Rapid Research Letters, 2014, 8, 871-875.	1.2	7
10	Performance of Nanocrystal ZnO thin film Schottky Contacts on Cu by Atomic Layer Deposition. IEEE Nanotechnology Magazine, 2016, , 1-1.	1.1	6
11	Electrical Characteristics of TiW/ZnO Schottky contact with ALD and PLD. Materials Research Society Symposia Proceedings, 2014, 1635, 127-132.	0.1	5
12	Defect Characterization of PEALD High- κ ZrO_2 Films Fabricated on III-V Materials. IEEE Transactions on Semiconductor Manufacturing, 2016, 29, 355-362.	1.4	5
13	Tetraallyltin precursor for plasma enhanced atomic layer deposition of tin oxide: Growth study and material characterization. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2019, 37, .	0.9	5
14	ZnO Schottky Nanodiodes Processed From Plasma-Enhanced Atomic Layer Deposition at Near Room Temperature. IEEE Transactions on Electron Devices, 2018, 65, 4513-4519.	1.6	3
15	Underlying design advantages for GaN MOSFETs compared with GaN HFETs for power applications. Journal of Computational Electronics, 2014, 13, 217-223.	1.3	2
16	Stoichiometry controlled homogeneous ternary oxide growth in showerhead atomic layer deposition reactor and application for $\text{Zr}_x\text{Hf}_{1-x}\text{O}_2$. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 2021, 39, 030401.	0.9	1
17	Optimization of Copper Schottky Contacts on Nanocrystalline ZnO thin films by Atomic Layer Deposition. MRS Advances, 2016, 1, 3421-3427.	0.5	0
18	Plasma enhanced atomic layer deposition and laser plasma deposition of ultra-thin ZnO films for Schottky barrier devices. , 2016, , .		0